

**PATENT** 

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Das et al.

Confirmation No.: 3570

Serial No.: 10/045,542

Group Art Unit: 1762

Filed: October 26, 2001

METHOD OF FABRICATING AN OXIDE LAYER ON A SILICON CARBIDE

LAYER UTILIZING AN ANNEAL IN A HYDROGEN ENVIRONMENT

Date: July 3, 2002

Commissioner for Patents Washington, DC 20231

## SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Sir:

For:

Attached is a form PTO-1449, together with a copy of the identified document(s). This Information Disclosure Statement is submitted in accordance with 37 C.F.R. § 1.97(b), within three months of the filing date of the above-referenced application or before the mailing of a first Office Action on the merits, whichever event occurs last. Accordingly, no fee is required. The Commissioner is authorized to charge any additional fee, or credit any refund, to our Deposit Account No. 50-0220.

Respectfully submitted,

Timothy J. O'Sullivan Registration No. 35,632

**Customer Number:** 

20792
PATENT TRADEMARK OFFICE

**CERTIFICATE OF MAILING** 

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, Washington, DC 20231 on July 3, 2002.

Traci A. Brown

Date of Signaturre: July 3, 2002